

AMAT Docket No. 2616 US/RTP/LE  
BSTZ Docket No. 004887.P090

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Guangcai Xing, et al.

Application No. 09/298,064

Filed: April 22, 1999

For: APPARATUS AND METHOD FOR  
EXPOSING A SUBSTRATE TO PLASMA  
RADICALS

Examiner: Rudy Zervigon

Art Unit: 1763

RESPONSE TO FINAL OFFICE ACTION

Box Amendments - No Fee  
Assistant Commissioner for Patents  
Washington, D.C. 20231

Dear Sir:

In response to the final Office Action mailed on November 6, 2002, Applicants respectfully request consideration of the following remarks.

IN THE CLAIMS

Presented herewith is a full set of the pending claims.

1. An apparatus comprising:  
a first reaction chamber,  
a gas source coupled to the first reaction chamber to supply a nitrogen gas to the first reaction chamber;  
an excitation energy source coupled to the first reaction chamber to generate a nitrogen plasma comprising ions and radicals from the nitrogen gas; and  
a second reaction chamber adapted to house a substrate for film formation at a site in the second reaction chamber,